

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	55604	memory and plurality with blocks	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/26 10:41
S2	553	S1 and reference adj cell	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/26 10:41
S3	278	S2 and reference near3 circuits	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/26 10:42
S4	54	S3 and plurality near sense	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/26 10:44
S5	213375	nonvolatile or non-volatile or non adj volatile	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/26 10:44
S6	43	S4 and S5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/26 11:06
S7	0	S6 and reference adj load	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/26 11:06

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transistor 103a of the selection circuit; and a comparator circuit 105 for comparing a voltage output from the reading memory cell 101b and a voltage output from the reference cell 103b.

Summary of Invention Paragraph - BSTX (15):
 [0014] In order to perform a reading operation from the reading memory cell 101b, the sense amplifier circuit 100 shown in FIG. 10 can include a charging circuit 106 for providing the drain electrode of the reading memory cell 101b with a bias voltage of the memory cell reading condition, and can also include a charging circuit 107 for providing the drain electrode of the reference cell 103b with a bias voltage of the memory cell reading condition.

Summary of Invention Paragraph - BSTX (17):
 [0016] As shown in FIG. 10, a gate voltage to be applied for performing the reading operation (hereinafter, referred to as a "reading gate voltage") is applied to the control gate electrode of the reading memory cell 101b selected by the selection transistor 101a. Simultaneously, a drain voltage to be applied for performing the reading operation (hereinafter, referred to as a "reading drain voltage") is applied to the drain electrode of the selected reading memory cell 101b through the selection transistor 101a by the charging circuit 106, transistor load 102a (FIG. 11) and the resistance load 102b (FIG. 12).

Summary of Invention Paragraph - BSTX (18):
 [0017] The charging circuits 106 and 107 operates until the drain electrode of the memory cell 101b and the drain electrode of the reference cell 103b obtain the drain voltage of the memory cell reading condition. After the drain voltage is reached, the charging circuits 106 and 107 stop operating. A source electrode of the selected reading memory cell 101b is grounded through a transistor or the like, and thus a current flows between the drain electrode and the source electrode of the selected reading memory cell 101b (hereinafter, this current will be referred to as a "reading current").

Summary of Invention Paragraph - BSTX (20):
 [0019] Substantially the same operation is performed for the reference cell 103b. As a result, a reference current flows between the drain electrode and the source electrode of the reference cell 103b. The reference current is converted into a voltage by the load of the current detection circuit 104, and the voltage is input to the other input end of the comparator circuit 105 (hereinafter, the voltage obtained from the reference current will be referred to as a "reference voltage").

Summary of Invention Paragraph - BSTX (21):
 [0020] The reading current of a selected reading memory cell 101b containing electrons in the floating gate electrode, i.e., the program cell, is smaller than the reference current. The reading current is converted into a voltage by

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(54) REFERENCE VOLTAGE GENERATION THE CIRCUIT FOR SEMICONDUCTOR MEMORY DEVICE, MEMORY READING CIRCUIT INCLUDING SAME, AND ELECTRONIC INFORMATION DEVICE INCLUDING THE SAME

(70) Inventor: Yoshinori Morikawa, Itozumi (JP)

(57) Abstract
 A reference voltage generation circuit includes at least one reference cell having a source electrode and a drain electrode; a plurality of first sense circuits connected to the reference cell and including an N-channel transistor, a P-channel transistor, a plurality of input ends and a plurality of output ends; and a plurality of second sense circuits each for receiving an output from a corresponding one of the plurality of first sense circuits, the plurality of second sense circuits each having a load circuit, an N-channel transistor, a plurality of input ends and a plurality of output ends.

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 (52) U.S. CL. 365/189,09

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TITLE: Semiconductor **memory** device

----- KWIC -----

Abstract Text - ABTX (1):

There is provided a semiconductor **memory** device in which the trouble in reading data due to an overshoot of a data signal can be avoided even when a reference signal for giving a reference for the determination a logical value of the data signal from a **memory** cell is constantly generated. This semiconductor **memory** device is constructed such that data is read by comparing a data signal from a **memory** cell with a reference signal from a **reference cell** in a differential-type sense amplifier. The semiconductor **memory** device comprises a feedback circuit for limiting a relative change between the reference signal and the data signal received by the differential-type sense amplifier. This feedback circuit momentarily feeds an output of the differential-type sense amplifier back to its input node, when data stored in the **memory** cell is read out, to thereby momentarily render the data signal and the reference signal equal to each other.

TITLE - TI (1):

Semiconductor **memory** device

Brief Summary Text - BSTX (3):

This invention relates generally to semiconductor **memory** devices such as a flash **memory**, an EPROM (Erasable and Programmable Read Only **Memory**) and a ROM (Read Only **Memory**), and more particularly to a semiconductor **memory** device of such type that data is read by comparing a data signal from a **memory** cell with a reference signal/reference voltage from a **reference cell**.

Brief Summary Text - BSTX (6):

In general, a semiconductor **memory** device such as a flash **memory** is constructed so that multi-bit (eight-bit, for example) can be inputted and outputted. A principal structure of a read system in a semiconductor **memory** device of such type is shown in FIG. 8. As shown in FIG. 8, a **memory** cell array 1100, comprising **non-volatile memory** cells (not shown) arranged in a matrix, is divided into blocks 1100-1 to 1100-8 in correspondence with data bits D0 to D7 of external data D, respectively.

Brief Summary Text - BSTX (7):

A **plurality** of word lines WL are arranged to extend in the row direction of the **memory** cell array 100 so as to pass through the blocks 1100-1 to 1100-8

(12) United States Patent
Ukubo

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(34) SEMICONDUCTOR MEMORY DEVICE
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(58) Field of Search 365/185.1, 185.2, 365/185.21, 205, 207, 210, 370/257

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22 Claims, 10 Drawing Sheets

US-PAT-NO: 5982662

DOCUMENT-IDENTIFIER: US 5982662

TITLE: Semiconductor memory characteristics for data having multi values

Abstract Text - ABTX (1):
 A semiconductor memory device is described that has an improved read characteristics. The semiconductor memory device includes a plurality of memory cells, a reference cell, a comparator located between the memory cells and the reference cell, and a discriminator coupled to the comparator. The comparator compares the actual signal equivalent to a value of a current flowing in each of the memory cells and reference signals equivalent to a value of a current flowing in the reference cell with each other to output a comparison result signal in each of data reading operation modes. The discriminator discriminates a value of data stored in each of the memory cells based on the comparison result signal. The discriminator includes a circuit shared for discrimination of a data value in each of the data reading operation modes.

TITLE - TI (1):
 Semiconductor memory device with improved read characteristics for data having multi values

Brief Summary Text - BSTX (3):
 The present invention relates generally to a semiconductor memory device. More particularly, this invention relates to a flash EEPROM (Electrical Erasable and Programmable Read Only Memory) with improved read characteristics for data having multi values.

Brief Summary Text - BSTX (5):
 Considerable attention has recently been given to non-volatile semiconductor memories, such as a ferro-electric memory EPROM (Erasable and Programmable Read Only Memory) and EEPROM (Electrically Erasable and Programmable Read Only Memory). To store data, an EPROM and EEPROM use a floating gate for storing charges and a control gate for detecting a change in threshold voltage according to the presence or absence of charges in the floating gate. EEPROMs include a flash EEPROM which can perform data erasure for the entire memory chip or partial data erasure for each of a plurality of blocks in the memory cell array. There are two general types of memory cells in a flash EEPROM: a split gate type and a stacked gate type.

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Fig. 21

heavy I-V circuit